

L Number	Hits	Search Text	DB	Time stamp
1	8682	(250/311,306,307,310,396R,397-399,396,491. USPAT1, 492.	US-PGPUB	2204/04/21 09:35
2	0	((250/311,306,307,310,396R,397-399,396,491. and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)) or ((250/311,306,307,310,396R,397-399,396,491. DERWENT;	EPO; JPO;	2004/04/21 09:36
3	270	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)) or ((250/311,306,307,310,396R,397-399,396,491. IBM_TDB	DERWENT;	2004/11/03
4	326	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)) or ((250/311,306,307,310,396R,397-399,396,491. EPO; JPO;	IBM_TDB	09:37
5	326	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. USPAT; US-PGPUB	USPAT;	2004/11/03
6	0	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	US-PGPUB	09:37
7	0	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. IBM_TDB	EPO; JPO;	2004/11/03
8	0	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	IBM_TDB	09:39
9	0	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. IBM_TDB	EPO; JPO;	2004/11/03
10	0	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	IBM_TDB	09:40
11	1	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	EPO; JPO;	2004/11/03
12	3	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	IBM_TDB	09:39
13	34	øf(mhakged ædþipæticle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491. DERWENT;	EPO; JPO;	2004/11/03
		or mask or reticle))) and ((shaped near2 beam) and (reflect\$4 and transmit\$5))	IBM_TDB	09:40

14	36	(((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped near2 beam) with (multi\$5 adj beam))) or (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped near2 beam) and (multiple adj beam))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:40 492.22, 492.3).ccls.)
15	1	(((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped' near2 beam) width(filet\$4adjbeam\$mit\$5))) (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped near2 beam) and (multiple adj beam))) or (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:45 492.22, 492.3).ccls.)
16	5	(((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped near2 beam) and (multiple adj beam))) or (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or (((250/311,306,307,310,396R,397-399,396,491 and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle)))) and ((shaped near2 beam) and (multiple adj beam))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:44 492.22, 492.3).ccls.)
17	1	6184526.pn. reticle))) and ((shaped near2 beam) and (reflect\$4 and transmit\$5)))	USPAT	2004/11/03 09:44
18	1	6184526.cpns and j1(\$ect\$on\$adj1\$near\$2\$ional) shap\$2\$shape\$B) (with angle\$angle\$2 or rectangle\$2))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53
19	0	6184526.pn. and (((cross adj1 sectional) near2 shape\$2) with (triang\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:49
21	0	6184526.pn. and (((multi\$3 adj2 apertur\$3) near3 array\$2) with mask\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53
22	0	6184526.pn. and (multi\$3 adj2 apertur\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53